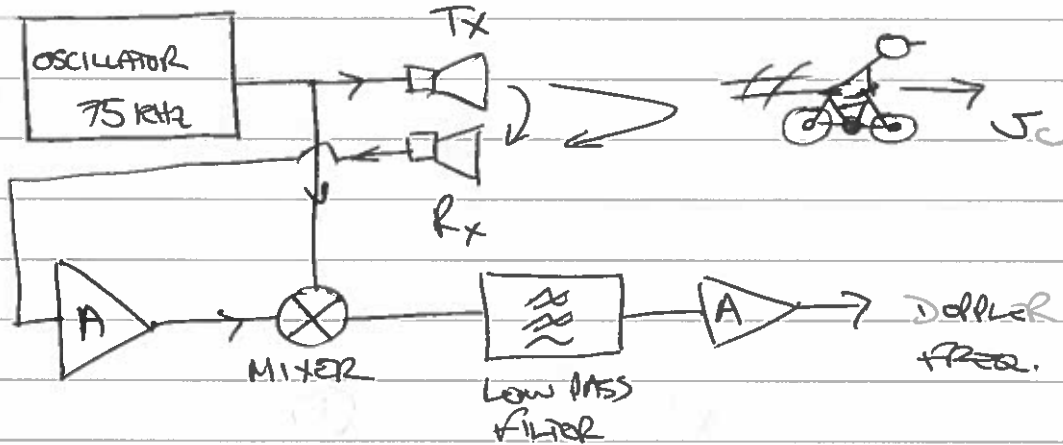


4B13 2016

1(a)



@ 75 kHz,  $\lambda = \frac{340}{75,000} = 4.53 \times 10^{-3} \text{ m}$

Every  $\lambda/2$  distance by cyclist gives 1 Doppler cycle

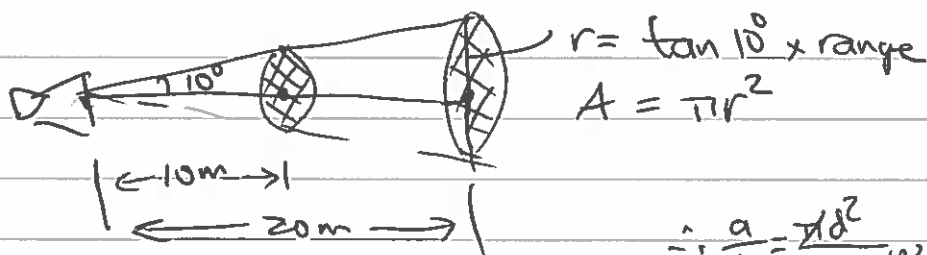
$\therefore f_{\text{Dop}} = \frac{v_c}{\lambda/2} = \frac{2v_c}{4.53 \times 10^{-3}} = 441 \text{ Hz / ms}^{-1}$   
 (25%) (= 2f \frac{v\_c}{v\_s})

(b) Assume cyclist back-scatters v/sonic isotropically into hemi-sphere.

v/sonic Tx power coupled into air =  $\frac{24}{150} \cdot \eta \cdot \frac{4 Z_T Z_{\text{air}}}{(Z_T + Z_{\text{air}})^2} = 0.347 \text{ W}$

( $Z_{\text{air}} = 340 \times 1.2 = 408 \text{ Ry/s}$ )

Range	Atten. (both ways)	Beam area
10m	$0.25 \times 2 \times 10 = 5 \text{ dB} = \times 0.316$	9.78 m <sup>2</sup>
20m	$0.25 \times 2 \times 20 = 10 \text{ dB} = \times 0.1$	39.1 m <sup>2</sup>



$\therefore \frac{a}{A} = \frac{\pi d^2}{4 \times 2 \pi R^2}$   
 $a = \pi d^2 / 4$

Assume  $Z_{\text{cyclist}}$  is very different to  $Z_{\text{air}} \therefore$  total reflection

(b) contd.

$\therefore$  Power scattered back to  $R_f \Rightarrow$

@ 10m :  $0.347 \times 0.316 \times 0.5 / 9.78 \times 0.05^2 / 8 \times 10^2 = 17.5 \mu\text{W}$

@ 20m :  $0.347 \times 0.1 \times 0.5 / 39.1 \times 0.05^2 / 8 \times 20^2 = 0.35 \mu\text{W}$

Coupled back to  $R_f$  and converted to electrical signal

10m :  $17.5 \times 10^{-9} \times 0.603 \times 10^3 = V_s^2 / 1000$

20m :  $0.35 \times 10^{-9} \times 0.603 \times 10^3 = V_s^2 / 1000$

$\therefore V_s = 1.25 \text{ mV} \Rightarrow 2.5 \text{ mV}$

$\therefore V_s = 0.18 \text{ mV} \Rightarrow 0.36 \text{ mV}$

Signal voltage amplitude

[35%]

(c)  $R = R_0 e^{-\beta'/T}$  @ 273K (°C)  $1000 = R_0 e^{\frac{3800}{273}}$

$\therefore R_0 = 9.01 \times 10^{-4} \Omega$

T (°C)	V (mV)
0	2.00
10	1.22
20	0.773 ← ang.
30	0.504

Take slope mid-range @ 20°C (or can use 10°C; will be larger non-linearly)  $\downarrow$

$\frac{dR}{dT} = -\frac{\beta' R_0}{T^2} e^{\beta'/T}$

$= -\frac{3800 \times 9.01 \times 10^{-4}}{293^2} e^{\frac{3800}{293}} = -17.1 \Omega/^\circ\text{C}$  or  $-29.0 \Omega/^\circ\text{C}$

$\times$  current @ 0.002 A  $\Rightarrow -34.2 \text{ mV}/^\circ\text{C}$  or  $-58.0 \text{ mV}/^\circ\text{C}$

$\therefore$  over 20°C range (10-30)  $\Rightarrow -0.684 \text{ V}$  signal change

linear  $\therefore 1.22 - 0.684 = 0.536 \text{ V}$

[25%]

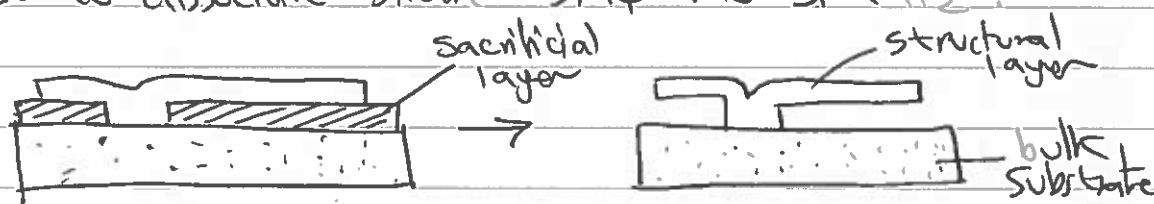
non-linearity =  $\frac{0.504 - 0.536}{0.504 - 0.536} = 0.047$  or 4.7%  
 $\frac{0.38}{0.536}$  or 38%

(d)  $f_{\text{exp.}} = \frac{v_c}{3 \times 10^8} \times 2 \times 24 \times 10^9 = 160 \text{ Hz/ms}^{-1}$

[15%]

will be more accurate as speed of light changes much less than speed of sound (proportionally).

2(a) Surface micro-machining involves construction of devices onto a silicon (usually), quartz or glass substrate by deposition and patterning of consecutive layers. A sacrificial layer of polymer (photoresist), metal or silicon oxynitride can be used to provide temporary support in device fabrication and then be removed later by reactive ion etching (RIE) or wet chemical processes. Structural layers of polysilicon are produced by chemical vapour deposition (low pressure gas reactions) at elevated temperatures  $200^{\circ}\text{C}+$  and/or plasma assist to dissociate silane  $\text{SiH}_4$  into  $\text{Si} + \text{H}_2$ .



For dry etching, a plasma comprising  $\text{CF}_4 + \text{O}_2$  can etch  $\text{Si}$  and  $\text{SiO}_2/\text{Si}_3\text{N}_4$  films using reactive ions to create directional or more isotropic etch conditions (for steep sides on features). When creating large structures, such as the proof mass for an accelerometer, holes are patterned in the layer to allow erosion underneath to reach the sacrificial layer.

A key technique in all these steps is the use of photolithography: spin on a polymer layer and selectively expose to UV light through a pattern mask. The UV exposure makes the photoresist polymer more or less soluble in the developer solution. Hence positive or negative patterns of the mask can be replicated. The photoresist is then used as an etch barrier for patterning the functional layers.

Monolithic integration of MEMS with CMOS electronics reduces the effects of parasitic capacitance by having short connections between the device and interface electronics. This improves signal-to-noise ratio and allows detection of v. small displacements and currents.

[30%]

2b) In open-loop mode an accelerometer proof mass deflects on a spring suspension, where the deflection is monitored by a differential capacitance arrangement of electrodes. The imbalance causes an output voltage - but it is only linear for small deflections. In closed loop mode, an additional set of capacitance plates maintains the proof mass in a fixed location by applying feedback forces, from voltages applied to the plates. The electronic feedback is more complex to implement, but improves linearity and signal processing can increase the apparent stiffness of the spring suspension - so raising the resonant frequency of the spring-mass system, resulting in higher bandwidth.

[15%]

$$2c(i) \quad f_{res} = \frac{1}{2\pi} \sqrt{\frac{s}{m}} = \frac{1}{2\pi} \sqrt{\frac{10 \text{ Nm}^{-1}}{2 \times 10^{-9} \text{ kg}}} = \underline{\underline{11.25 \text{ kHz}}}$$

$$F = ma = 2 \times 10^{-9} \cdot 20 = 40 \text{ nN} = 100C \Rightarrow C = 4 \text{ nF}$$

[20%]

$$(ii) \quad \text{total capacitance, } C_t = \frac{A\epsilon_0}{d} = \frac{8.854 \times 10^{-12} \text{ F/m} \cdot 100 \cdot 600 \times 10^{-6} \cdot 7 \times 10^{-6}}{10^{-6}} = 3.72 \text{ pF}$$

$$\therefore C_t = 3.72 \text{ pF} \quad \text{so} \quad C_{sense} = 1.86 \text{ pF} = C_{force}$$

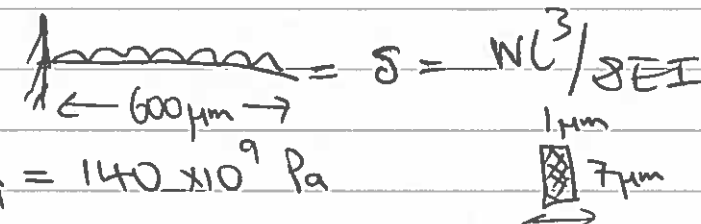
$$F = \frac{dE}{dx} \quad \text{where } E = \frac{1}{2} CV^2, \quad C = \frac{A\epsilon_0}{x}$$

$$\therefore \frac{dC}{dx} = -\frac{A\epsilon_0}{x^2} = -\frac{C}{x} \Rightarrow F = \frac{1}{2} \frac{C}{x} V^2$$

$$\text{to balance accel. } F = ma = 2 \times 10^{-9} \cdot 20 = 40 \text{ nN}$$

$$[20\%] \quad \text{so with } C = 1.86 \text{ pF}, x = 1 \mu\text{m} \Rightarrow \underline{\underline{V = 0.207 \text{ V}}}$$

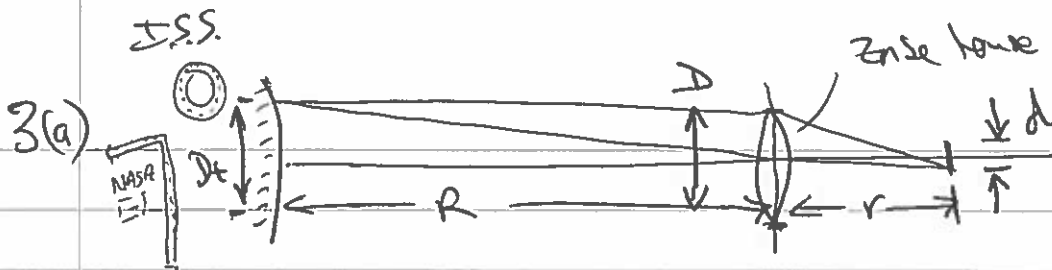
$$(iii) \quad \delta = \frac{WL^3}{8EI} \quad W = \frac{40 \times 10^{-9}}{50} = 8 \times 10^{-10} \text{ N}$$



$$E_{Si} = 140 \times 10^9 \text{ Pa} \quad I = \frac{1}{12} bd^3 = 5.23 \times 10^{-25} \text{ m}^4$$

[15%]

$$\therefore \delta = \underline{\underline{0.26 \mu\text{m}}}$$



$$W = \epsilon \sigma_{SB} T^4$$

$$\Delta W = W \frac{\pi}{16} \frac{d^2 D^2}{r^2}$$

$$T = 173 \text{ or } 373 \text{ K}$$

$$D = 0.05 \text{ m}$$

$$r = 0.1 \text{ m}$$

$$d = 0.005 \text{ m}$$

$$R = 10 \text{ m}$$

$$\therefore \Delta W = 0.5 \cdot 5.67 \times 10^{-8} \cdot T^4 \cdot \frac{\pi}{16} \frac{0.005^2 \cdot 0.05^2}{0.1^2}$$

$$\text{rand pixel} = 3.48 \times 10^{-14} T^4$$

[25%] square pixel  $4.43 \times 10^{-14} T^4$

$$\Rightarrow 31 \mu\text{W} \text{ to } 674 \mu\text{W}$$

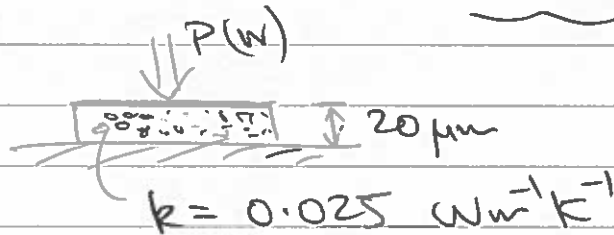
ie: change 643  $\mu\text{W}$

(b) By similar triangles:  $\frac{D_e}{R} = \frac{d}{r}$   $\Rightarrow \frac{\pi}{4} \Rightarrow 818 \mu\text{W}$

$$\therefore D_e = 10 \cdot \frac{0.005}{0.1} = 0.5 \text{ m}$$

This is divided into 100 pixels = 5mm/pixel on surface  
 [10%] of space station  $\therefore$  can see 5mm min. feature size

(c) (i)



sensor temp. rise,  $\Delta T$

$$P = \frac{kA\Delta T}{d} \quad \therefore \frac{\Delta T}{P} = \frac{d}{kA} = \frac{20 \times 10^{-6}}{0.025 \cdot 25 \times 10^{-6}} = 32 \text{ }^\circ\text{C/W}$$

from (a)

$$\Delta W = 3.48 \times 10^{-14} T^4$$

$$\Rightarrow 193 \mu\text{W} @ 0^\circ\text{C} \quad \Delta P = 30 \mu\text{W}$$

$$223 \mu\text{W} @ 10^\circ\text{C}$$

$$\therefore V_{\text{sens}} = 30 \times 10^{-6} \cdot 32 \cdot 50 \times 10^{-6} = 4.8 \text{ nV for } 10^\circ\text{C change.}$$

[20%]

$$\frac{\pi}{4} = 61 \text{ nV}$$

3(c)(ii) we need the thermal time constant for the sensor  
 ans: temp. difference across polymer layer

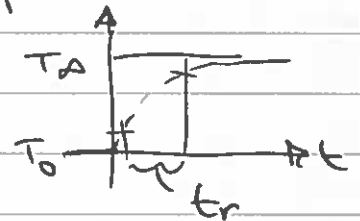
Heat flux,  $F = \frac{kA \Delta T}{d} = mc \frac{dT}{dt}$  where  $\Delta T = T_{\infty} - T$

So,  $\frac{kA(T_{\infty} - T)}{mc d} = \frac{dT}{dt}$  with  $\gamma = \frac{mc d}{kA}$

and  $T' = T - T_{\infty}$

$-T' = \gamma \frac{dT'}{dt}$  soln.  $\ln T' = -\frac{t}{\gamma} + C$

Boundary condns  $T = T_0$  @  $t = 0$   
 $T = T_A$  @  $t = A$



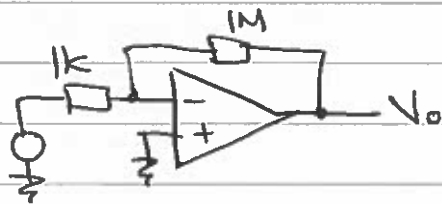
$\therefore T = (T_0 - T_A) e^{-t/\gamma} + T_A$

So, the rise-time  $t_r = 2.2\gamma$  and  $f_{-3dB} \approx \frac{1}{2\pi\gamma}$

Hence, with  $\gamma = \frac{mc d}{kA} = \frac{10^{-6} \cdot 450 \cdot 20 \cdot 10^{-6}}{0.025 \cdot (5 \cdot 10^{-3})^2} = 14 \text{ ms}$

[20%] So,  $f_{-3dB} \approx 11 \text{ Hz}$  max. response rate ( $t_r = 32 \text{ ms}$ )

(d)



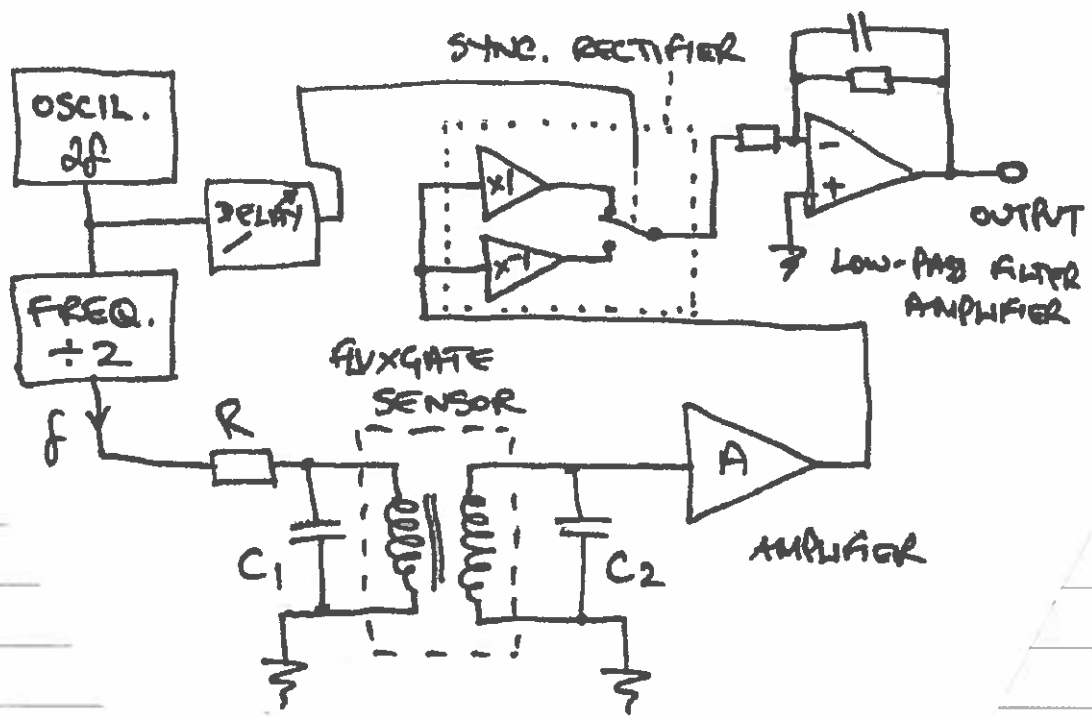
$B = 11 \text{ Hz}$ ,  $T = 273 \text{ K}$   
 $k = 1.38 \times 10^{-23} \text{ J/K}$

$V_{\text{noise in}}$	Gain	$V_{\text{out}}$ ( $\mu\text{V rms}$ )
$\sqrt{4kTRB}$ , $1k\Omega$	$\times 1000$	12.9
$10^{-9} \sqrt{B}$ , $V_n$	$\times 1000$	0.41
$0.3 \cdot 10^{-12} \times R \sqrt{B}$ , $i_n$	$\times 1000$	3.32
	$\times 1000$	0.99

$\sqrt{\sum v_n^2} = 13.4 \mu\text{V rms}$  (total noise)

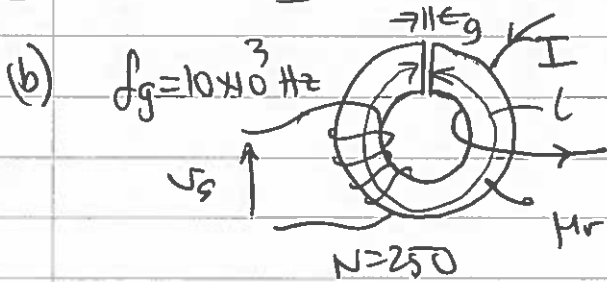
[25%] From part (c)(i) signal  $\approx 6.1 \text{ nV}/^\circ\text{C} \times 1000 \text{ gain} = 6.1 \mu\text{V}/^\circ\text{C}$   
 $\therefore$  min. detectable  $\Delta T \approx 13.4/6.1 \approx 2^\circ\text{C}$

4(d)



The flux-gate magnetometer utilises a saturable magnetic core, periodically excited with a drive waveform via a coil coupled to the core. Another winding, or the same coil, monitors the flux in the core via an induced voltage waveform. If an external field also couples to the core, then an offset is introduced into the B-H characteristic - resulting in even harmonics being induced in the sensing coil voltage. The magnitude of these even (usually 2<sup>nd</sup>) harmonics is proportional to the external field.

[20%]



$$g = 0.25 \times 10^{-3} \text{ m}$$

$$L = 25\pi \times 10^{-3} \text{ m}$$

$$A = 80 \times 10^{-6} \text{ m}^2$$

$$\mu_r = 7500$$

$$B = B_{air} = B_{core} = \mu_0 H_{air} = \mu_0 \mu_r H_{core} \quad I = L H_{core} + g H_{air}$$

$$\therefore I = H_{air} \left( \frac{L}{\mu_r} + g \right) \Rightarrow B = \frac{\mu_0 I}{\left( \frac{L}{\mu_r} + g \right)}, \quad \phi = BA$$

$$V_s = N \frac{d\phi}{dt} = \frac{N \mu_0 A I}{\left( \frac{L}{\mu_r} + g \right)} \cdot \frac{2\pi f g}{2} \cdot \frac{2}{\pi}$$

$\uparrow$  set by gating drive  $\approx 2\pi f \phi$ 
 $\uparrow$   $\div 2$  as only 1 core
 $\uparrow$  sync. rect. average of  $1/2$  sine

$$\mu_{eff} = 3846 = \frac{1}{2.60 \times 10^{-4}}$$

4(b) contd.  $V_s = \frac{250 \cdot 4\pi \times 10^{-7} \cdot 80 \times 10^{-6} \cdot 10^4 \cdot 2 \cdot I}{\left( \frac{\pi \times 25 \times 10^{-3}}{7500} + 0.25 \times 10^{-3} \right) \pi}$

$\therefore \frac{V_s}{I} = 1.93 \text{ V/A}$

[25%]

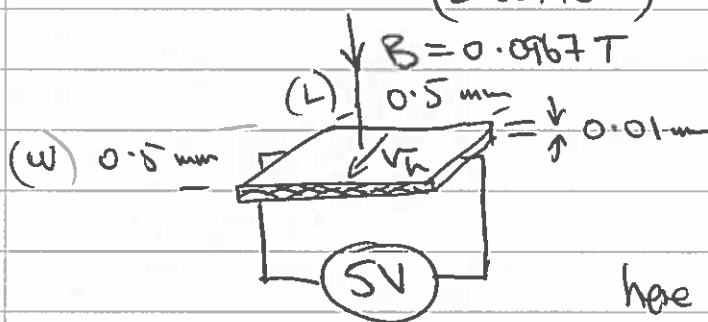
(c)  $V_c = n \frac{d\phi}{dt} = 250 \cdot \frac{d}{dt} \left( \mu_0 I / \left( \frac{L}{\mu_{eff}} + g \right) \right) \cdot 80 \times 10^{-6}$

$\therefore V_c = \frac{0.02 \mu_0}{2.60 \times 10^{-4}} \cdot \frac{dI}{dt} = 9.65 \times 10^{-5} \frac{dI}{dt}$

$= 6.06 \times 10^{-4} \int I dt$

[15%]

(d) @ 20A  $\Rightarrow B = \frac{\mu_0 \cdot 20}{(2.60 \times 10^{-4})} = 0.0967 \text{ T in gap}$

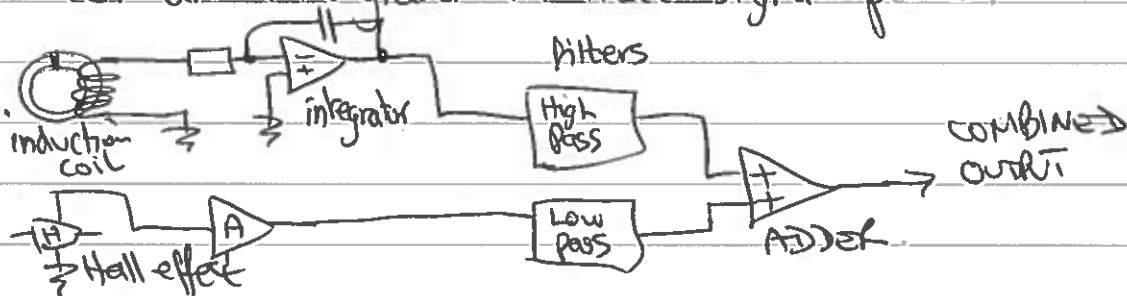


Hall sensor carrier force balance:  $\frac{V_H}{w} q = \frac{B V \mu q}{L}$

hence  $w = L \therefore V_H = B V \mu$

[20%]  $V_H = 0.0967 \cdot 0.16 \cdot 5 = 77.4 \text{ mV}$

(e) In order to remove the freq. dependency of the induction coil signal, there is a requirement for a 1/f response i.e. an integrator in that signal path.



From notes, for Hall sensor simple diffusion analysis  $\tau = \frac{w^2}{8D}$  where  $D = \mu kT/q$  and  $f_{3dB} = \frac{1}{2\pi\tau} = 20.6 \text{ kHz}$

[20%] So induction coil signal should cut in above  $\approx 20 \text{ kHz}$



**Q1 Ultrasonic Doppler sensing and thermistors**

A popular question which was well answered by most. The Doppler system schematic was fairly straightforward and most candidates made a good attempt at calculating the received signal levels, although a few omitted to apply the attenuation in both directions. The non-linearity of the thermistor signal was not well derived in many cases and, in the last part, few realised that the speed of light varies less proportionally than the speed of sound does over typical environmental conditions.

**Q2 MEMS fabrication, device resonance & noise**

A quite well-answered question on MEMS fabrication (surface micro-machining), with most candidates knowing the main steps, however process details were often missing. The estimate of resonant frequency was also generally well done, but few calculated the beam deflection correctly in the final part. The sensing voltage feedback was generally quite well understood.

**Q3 Pyrometer system and electronics noise budget**

A very popular question, which was well answered in most cases. The pyrometer analysis was generally correctly done assuming either square or round pixels; both were acceptable. The final part on circuit noise was well answered by many candidates, although the bandwidth assumptions were sometimes a little wide of the mark.

**Q4 Fluxgate & Hall effect current sensors**

This was the least popular question, but which attracted some high quality attempts - although some candidates failed to calculate the flux density and Hall sensor responsivity correctly. Many recalled the Hall effect sensor equations – or at least remembered the end result to use for the bandwidth estimate. The fluxgate schematic was generally well recalled as was its responsivity equation.

P. A. Robertson (Principal Assessor)